

Title (en)

PLASMA ENHANCED CHEMICAL VAPOR DEPOSITION APPARATUS AND METHOD

Title (de)

-VORRICHTUNG UND VERFAHREN ZUR PLASMAUNTERSTÜTZTEN CVD

Title (fr)

APPAREIL ET PROCEDE DE DEPOT DE VAPEUR CHIMIQUE AMELIORE AU PLASMA

Publication

EP 1799879 A1 20070627 (EN)

Application

EP 04784214 A 20040914

Priority

US 2004030275 W 20040914

Abstract (en)

[origin: WO2006031234A1] A substrate processing system includes a deposition chamber (102) and a plurality of tubular electrodes (126) positioned within the deposition chamber (102) defining plasma regions (128) therebetween.

IPC 8 full level

C23C 16/54 (2006.01)

CPC (source: EP)

C23C 16/24 (2013.01); **C23C 16/45578** (2013.01); **C23C 16/509** (2013.01); **C23C 16/54** (2013.01); **H01J 37/32009** (2013.01); **H01J 37/32541** (2013.01)

Citation (search report)

See references of WO 2006031234A1

Designated contracting state (EPC)

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